

(19)



Europäisches Patentamt  
European Patent Office  
Office européen des brevets



(11) Publication number:

**0 593 966 A1**

(12)

**EUROPEAN PATENT APPLICATION**(21) Application number: **93115996.6**(51) Int. Cl.<sup>5</sup>: **H01L 23/538, H01L 25/065**(22) Date of filing: **04.10.93**(30) Priority: **19.10.92 US 963346**(43) Date of publication of application:  
**27.04.94 Bulletin 94/17**(84) Designated Contracting States:  
**DE FR GB**(71) Applicant: **International Business Machines Corporation**  
**Old Orchard Road**  
**Armonk, N.Y. 10504(US)**(72) Inventor: **Beaman, Brian Samuel**  
**3 Stoutenburg Drive**  
**Hyde Park, N.Y. 12538(US)**  
Inventor: **Doany, Fuad Elias**  
**125 Cedar Road**  
**Katonah, N.Y. 10536(US)**  
Inventor: **Fogel, Keith Edward**  
**5 Broadlyn Court**  
**Bardonia, N.Y. 10954(US)**  
Inventor: **Hedrick Jr., James Lupton**  
**6799 Chelton Drive**  
**Oakland, CA 94611(US)**  
Inventor: **Lauro, Paul Alfred****8 Central Drive,**  
**Apt. 4****Nanuet, N.Y. 10954(US)**Inventor: **Norcott, Maurice Heathcote****429 Sierra Vista Lane****Valley Cottage, N.Y. 10989(US)**Inventor: **Ritsko, John James****70 High Ridge Road****Mount Kisco, N.Y. 10549(US)**Inventor: **Shi, Leathen****45 Oslo Drive****Yorktown Heights, N.Y. 10549(US)**Inventor: **Shih, Da-Yuan****16 Vervalen Drive****Poughkeepsie, N.Y. 12603(US)**Inventor: **Walker, George Frederick****1540 York Avenue, nr. 11K****New York, N.Y. 10028(US)**(74) Representative: **Mönig, Anton, Dipl.-Ing.**  
**IBM Deutschland Informationssysteme GmbH,**  
**Patentwesen und Urheberrecht**  
**D-70548 Stuttgart (DE)**(54) **Three dimensional high performance interconnection package.**

(57) The present invention is directed to a structure (2) for packaging electronic devices, such as semiconductor chips (36, 38), in a three dimensional structure which permits electrical signals to propagate both horizontally and vertically. The structure is formed from a plurality of assemblies (4, 6). Each assembly is formed from a substrate (8) having disposed on at least one surface a plurality of electronic devices. Each assembly is disposed in a stack of adjacent assemblies. Between adjacent assemblies there is an electrical interconnection means (49) electrically interconnecting each assembly. The electrical interconnection means is formed from an elastomeric interposer. The elastomeric interposer is formed from an elastomeric material having a plural-

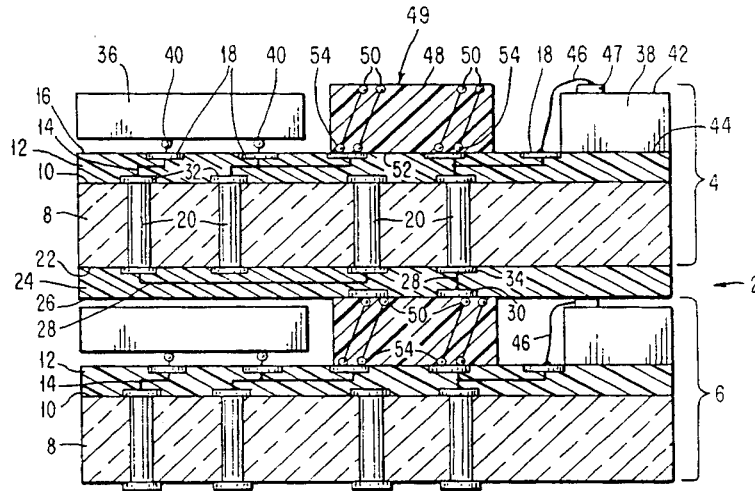
ity of electrical conductors extending therethrough, either in a clustered or un-clustered arrangement. The electrical interconnection means is fabricated having a plurality of apertures extending therethrough. The array of apertures corresponds to the array of electronic devices on the substrates. The aperture and electrical interconnection means is disposed over the array of electronic devices so that the electrical interconnection means is between adjacent electronic devices. The stack of assemblies is compressed thereby compressing the electrical interconnection means between adjacent assemblies. The substrate of each assembly is formed from a thermally conductive material such as diamond. A heat dissipation means is thermally connected to the

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edges of the substrate to extract heat generated within the structure. Methods for fabricating the electrical interconnection means as a stand alone elastomeric sheet are described. The ends (50, 54) of the plurality of conductors in the electrical interconnection means (49) are fabricated so that upon

compression between adjacent assemblies (4, 6) there is a wiping action between the conductor ends (e.g. 50) and contact locations (e.g. 30) on the adjacent assemblies to form a good electrical contact therewith.

FIG. 1



1 The present invention is directed to packaging structures for interconnecting electronic devices in a three dimensional structure. More particularly, the present invention is directed to a structure having a plurality of substrates wherein each substrate has a plurality of electronic devices thereon forming an assembly. There are a plurality of assemblies disposed one on top of each other with a vertical wiring interconnection structure disposed between adjacent assemblies. Most particularly, the vertical wire interconnection structure contains a plurality of electrical conductors disposed in an elastomeric material and is compressed between adjacent assemblies.

In the microelectronics industry, integrated circuits, such as semiconductor chips, are mounted onto packaging substrates to form modules. In high performance computer applications, these modules contain a plurality of integrated circuits. A plurality of modules are mounted onto a second level of packages such as a printed circuit board or card. The cards are inserted in a frame to form a computer.

In nearly all conventional interconnection packages except for double sided cards, signals from one chip on the package travel in a two dimensional wiring net to the edge of the package then travel across a card or a board or even travel along cables before they reach the next package containing the destination integrated circuit chip. Therefore, signals must travel off of one module onto wiring on a board or onto wiring on a cable to a second module and from the second module to the destination integrated circuit chip on the module. This results in long package time delays and increases the wireability requirement of the two dimensional wiring arrays.

An improvement in interchip propagation time and increase in real chip packaging density can be achieved if three dimensional wiring between closely spaced planes of chips could be achieved.

US Patent application 5,099,309 describes a three dimensional semiconductor chip packaging structure which comprises a plurality of stacked cards. Each card is specially fabricated to have cavities on both sides thereof which contain chips. On each surface of the card, there are electrical conductors which are bonded by wires to contact locations on the chips. Electrical conductors extend through the cards between the chip containing regions and to contact locations on each side of the card. These contact locations have dendrites on the surface. The cards are stacked so that the dendrite covered contact locations on adjacent sides of adjacent cards intermesh to provide electrical interconnection between the adjacent cards. This structure requires a high degree board flatness for the connections to be mated.

2 The invention as claimed provides improved three dimensional integrated circuit packaging structures. The proposed packaging structures provide both horizontal electrical interconnections and compliant vertical electrical interconnections. The advantages achieved by the invention include that such structures can be assembled and disassembled into a plurality of subassemblies, provide high thermal dissipation capacity, do not require rigid electrical interconnection between subassemblies, and allow to be fabricated using conventional packaging substrates.

A broad aspect of the present invention is a structure having a plurality of assemblies. Each of the assemblies is formed from a substrate having a first and second opposing surfaces. There are a plurality of electronic devices disposed on at least one of the first and second surface of the substrate of each assembly. Each of the plurality of assemblies is disposed adjacent another of the plurality of assemblies so that the first surface of one of the adjacent assemblies is adjacent the second surface of the other of the adjacent assemblies. An electrical interconnection means is disposed between the first and second surfaces of the adjacent assemblies and provides electrical interconnection between contact locations on the adjacent surfaces. The electrical interconnection means is formed from a dielectric material having first and second opposing surfaces and a plurality of electrical contact locations on each surface which are electrically interconnected by a plurality of electrical conductors extending from the first surface to the second surface of the electrical interconnection means.

In a more particular aspect of the present invention, the substrates of the assemblies are formed from a diamond like material which has high thermal dissipation capacity.

In another more particular aspect of the present invention, the substrates have a plurality of dielectric and electrically conducting layers.

In another more particular aspect of the present invention, a heat dissipation means dissipates heat generated in the structure.

These and other objects, features and advantages of the present invention will become apparent upon further consideration of the following detailed description of preferred embodiments of the invention when read in conjunction with the figures, in which:

Figure 1 shows a side view of a three dimensional electronic device packaging structure according to the present invention.

Figure 2 shows a partial perspective view of the structure of Figure 1.

Figure 3 shows a top view of the electrical interconnection means of the structure of Figure 1.

Figure 4 shows a perspective view of the structures of Figure 1 including a heat dissipation means.

Figure 5 shows a cross sectional view of a section of the electrical interconnection means of the structure of Figure 1.

Figure 6 shows the structure of Figure 5 disposed under pressure between two adjacent substrates.

Figure 7 shows another embodiment of the structure of Figure 5 having grooves on the two opposing surfaces.

Figure 8 shows grooves on an interposer engaging projections on a substrate to align substrate and interposer contact locations.

Figure 9 shows an alignment frame for mating with alignment grooves such as shown in the structure of Figure 10.

Figure 10 shows an interconnection structure having grooves for mating with the frame of Figure 9.

Figure 11-19 show the process for making the electrical interconnection means, for example, of Figure 5.

Figures 20 and 21 show an alternate embodiment of some of the method steps for fabricating an electrical interconnection means.

Figure 22 schematically shows an optical system to form balls on the end of the wire conductors in Figure 15.

Figure 23 is an enlarged view of the region of Figure 7 enclosed in dashed circle 230.

Figure 1 shows structure 2 according to the present invention having two subcomponent assemblies 4 and 6. Structure 2 can have any number of subcomponent assemblies. Each subcomponent assembly is formed from a substrate 8 having a surface 10 which has a multilevel wiring structure 12 formed thereon. Multilevel wiring structure 12 is formed from a dielectric material, such as an oxide, a glass, a polymer and a ceramic, most preferably a polyimide polymer. Multilevel wiring structure 12 contains at least one layer of electrical conductors 14, such as copper, aluminum and gold, and has on surface 16 a plurality of contact locations 18. Substrate 8 is shown in Figure 1 as having vias 20 extending from surface 10 to surface 22. Surface 22 has a multilayer wiring structure 24 which is similar to multilayer wiring structure 12. Surface 26 of multilayer wiring structure 24 contains at least one electrically conductive layer 28 which is preferably copper, the dielectric material being preferably polyimide. Surface 26 has a plurality of electrical contact locations 30 which are preferably copper coated with gold. Electrical contact layers 18 are also preferably copper with a top coating of gold.

Substrate 8 can be any commonly used multilayered packaging substrate containing a plurality of electrical conductors or glass ceramic and is preferably a highly thermally conductive material such as synthetic diamond, aluminum nitride ceramic, silicon, a metal (such as copper) with an electrically insulating coating. Substrate 8 preferably has electrically conductive studs or vias 20 or through holes with a sidewall plated with an electrical conductor, such as copper, palladium, platinum and gold, as is commonly known in the art.

The electrical conductors in multilayer structures 12 on surface 10 of substrate 8 are electrically interconnected to contact locations 32 which are connected to via or stud 20 in substrate 8. Electrical conductors 28 in multilayer structure 24 on surface 22 of substrate 8 are electrically interconnected to contact locations 34 which are electrically interconnected to vias or studs 20 in substrate 8. Contact locations 32 and 34 are preferably formed from copper having a top surface of gold.

A plurality of electronic devices 36 and 38, such as integrated circuit chips, preferably semiconductor chips, are mounted onto surface 16 of multilayer wiring structure 12.

Electronic device 36 is mounted in a flip-chip configuration onto surface 16 with solder mounds 40, commonly known as C4s, electrically interconnecting the electronic device 36 to the contact locations 18.

Electronic device 38 is mounted with active face 42 facing upwards and its nonactive face 44 in contact with surface 16 of multilayer structure 12. Alternatively, for better thermal contact to substrate 8, device 38 may be mounted directly with its nonactive face 44 in contact with surface 10 of substrate 8. This is accomplished by removing a section of multilayer structure 12. Wires 46 commonly made of aluminum or gold are bonded between contact location 18 and contact location 47 on surface 42 of electronic device 38. Wires 46 are bonded by commonly known wire bonding techniques, ultrasonic bonding techniques, laser bonding techniques and the like.

Disposed between electronic devices 36 and 38 there is an electrical interconnection means 49 details of which will be described hereinbelow.

The electrical interconnection means 49 has a top surface 48 having contact locations 50 and a bottom surface 52 having contact locations 54. Contact locations 54 are in electrical interconnection with contact locations 18 between chips 36 and 38. Contact locations 50 are in electrical interconnection with contact locations 30 on surface 26 of multilayer structure 24.

Figure 2 shows a partial view of the structure of Figure 1 in perspective with a region of the right forward most corner of each substrate 8 partially

cut away to reveal vias or studs 20. On surface 16, there is seen contact locations 18 and electrical conductors 60 which electrically interconnect some of the contact locations 18. The electrical interconnection means 49 is shown only partially as a plurality of electrical conductors 62 and 64. The electrical interconnection means will be described in greater detail hereinbelow.

Figure 3 shows a top view of one of the sub-component assemblies 4 or 6 of Figure 1 showing the electrical interconnection means 49 having a plurality of apertures 66. The apertures 66 are adapted to receive a plurality of electronic devices 68 which are disposed on surface 16 of multilevel wiring structure 12 of Figure 1. Numbers common between Figures 1, 2 and 3 represent the same thing.

Figure 4 shows a perspective view of the structure shown in Figure 1 plus heat dissipation means 51 and 53. Numbers common between Figures 1, 2, 3 and 4 represent the same thing. Heat dissipation means 51 and 53 are in thermal contact with substrates 8. The heat dissipation means is preferably made of aluminum. Substrate 8 is held in grooves in heat dissipation means 51 and 53 to ensure good thermal contact, mechanical support and compresses the interconnection means 49 between adjacent assemblies to provide electrical interconnection therebetween as described herein below. Heat dissipation means 51 and 53 are held in a support frame (not shown).

The thin film wiring layers 12 and 14 of Figure 1 preferably contain at least one plain pair (XY) of wiring and two reference planes which provide power and ground to the electronic devices 36 and 38. If the electronic devices are bipolar chips there are preferably two additional power planes. The dimensions of the wiring and the thickness of the reference planes depends on the specific application and it can vary from 8 micron wide lines, 5 micron thick, on a 25 micron pitch to 25 micron wide lines, 25 microns thick on a pitch of 75 micron or more. The thickness of the insulation in the thin film wiring layers 12 and 24 is adjusted to provide the required transmission line impedance that is typically in the range of 4 to 80 ohms.

The electrical interconnection means 49 is formed to occupy the space between the chips as shown in Figures 1-4. The structure of Figure 1 is compressed from the top and bottom of the structure to compress the electrical interconnection means 46 between the adjacent assemblies pressing electrical contact locations 30 on substrate 8 in contact with electrical contact locations 50 on electrical interconnection means 49 and pressing electrical contact locations 54 on electrical interconnection means 49 in contact with electrical contact locations 18 on the surface of the thin film wiring

layer 12. Thus, a signal from any one chip will travel in the thin film wiring layer and vertically through the electrical interconnection wiring means 49 to any thin film wiring plane in the stack of substrates 8 and thus along the shortest path to any chip in the entire structure 2. If a single plane contained 25 chips, for example, as shown in Figure 3, each being 1 centimeter square, then the electrical interconnection means 46 would occupy the 1 centimeter space between each chip. With this design point the vias in the substrates 8 and the connections in the electrical interconnection means 49 could be made on a 0.9 mm (36 mil) square grid with 0.5 mm (20 mil) wide pads 18 on the substrate 8. There would be approximately 6,694 vertical signal connections possible on one plane. The grid could be reduced by a factor of approximately 2 if required and 26,000 vertical connections could be made.

The overall high performance package can consist of as many insulating plates populated by chips as required. The heat would be conducted to the edges of the high thermal conductivity substrates 8 where it would be carried away by air or water cooled or the like heat sinks as appropriate and commonly known in the art.

The substrates are preferably made of a high thermally conductive insulating material made of commercial diamond (manufactured for example by NORTON Inc. and Diamonex Inc.) which can be laser drilled to form vias and metallized for through hole connections using standard processing such as the process used on diamond heat spreaders for diode lasers. The very high thermal conductivity of diamond (1500 W/m<sup>2</sup>K) makes it the most desirable material in this structure and would allow the cooling of more than 100 watts per plane. Other materials are useful. A lower cost alternative would be AnN ceramic with co-sintered solid vias, which are commercially available or silicon wafers which can contain laser drilled holes or chemically etched through vias. The thin film wiring layer 12 and 24 preferably contains copper wiring in a polyimide dielectric and can be fabricated by standard sequential thin film processes directly onto substrate 8 as described in R. Tummala and E. Rymaszewski, Microelectronics Packaging Handbook, Van Nostrand, Rienhold, NY, 1989 Chapter 9, the teaching of which is incorporated herein by reference. The thin film wiring structure can be fabricated separately by the serial/parallel thin film wiring process and joined to the substrates 8 as described in US Patent application, Serial No. 07/695,368, filed May 3, 1991, the teaching of which is incorporated herein by reference. In the serial/parallel processes the thin film wiring structures are fabricated on separate carriers then transferred and laminated to the insulated plates prefer-

ably by thermal compression bonding. The electrical interconnection means 49 preferably contains gold wires held at a slight angle in an elastomeric matrix. Other embodiments of large area array connectors can also work. The electrical interconnection means 49 using an elastomeric matrix has desirable properties such as lower resistance, low contact force, wipe, and low inductance which makes it particularly desirable in this application. The electrical interconnection means 49 can be fabricated to be approximately 1 millimeter thick with 10 percent compliance.

The substrates 8 are made with conducting vias. Top and bottom surface pads are applied by standard techniques such as evaporation of metals through a metal mask as described in Tiemmla et al., chapter 9 above. The electronic devices 36 and 38 are joined to each thin film wiring layer after the electronic devices are tested and burned in. The electrical interconnection means 49 are fabricated separately and tested. Finally, the stack of assemblies with electronic devices mounted onto the substrates with the electrical interconnection means 49 disposed thereon are aligned and a compressive force is applied to make the interconnections. The force is preferably from 10 to 50 grams per contact or from 70 to 300 kilograms for the entire package. The connection is separable.

Figures 5-21 show the method for fabricating electrical interconnection means 49 of Figure 1 and show various embodiments and fabrication techniques of this electrical interconnection means.

Figure 5 shows electrical interconnection means 80 which corresponds to electrical interconnection means 49 of Figure 1. The electrical interconnection means 80 is formed from an elastomeric material 82 having a plurality of electrical conductors 84 extending from side 86 to side 88 thereof. Each conductor 84 preferably has a generally spherical end 90 at side 86 and a flattened spherical shape 92 at side 88. The conductors 84 are preferably gold, gold alloy or copper alloy. The size, shape and the spacing of wires 84 along with the material properties of the elastomeric material 82 can be modified to optimize the connector for a specific application.

Figure 6 shows substrate 94 and 96 pressed towards each other as indicated by arrows 98 and 100 with interposer 80 therebetween. The elastomer 82 acts as a spring to push the enlarged end contact surfaces 90 and 92 against mating contacts 104 and 106 on substrates 94 and 96 respectively. Surface 102 of substrate 94 has contact locations 104 which are typically metallized pad. Substrate 96 has contact locations 106 which are also typically metallized pads. When substrate 94 is pressed towards substrate 96 the ends 90 and 92 move laterally with respect to the contact

surface because conductors 84 are at a nonorthogonal angle with respect thereto. This lateral movement results in a wiping action which breaks a surface oxide which is on the surface of the contact locations 104 and 106 and which is on the surface of the enlarged ends 90 and 92. The wiping action makes a good electrical contact between the enlarged surface 90 and 92 and the contact locations 104 and 106, respectively.

The advantages and unique features of the electrical interconnection means 80 are that it provides uniform spacing of the electrical conductors 84 and the elastomer material on, for example, a 0.2 mm (0.008 inch) minimum pitch using a single wire per contact. The enlarged ball shaped contacts 90 protrude from top side 86 of interconnection means 80 and the enlarged, flattened contacts 92 are generally flush with the bottom surface 88 of interconnection means 80. Textured or raised contact surface can be formed on the bottom side of the contact 92 to enhance the contact interface to an electrical contact location on substrate 96. The wires 84 in the elastomer material 82 can be grouped into small clusters to provide redundant connections for each contact location 104 or 106. If clustered wires are used, wires 95 in interconnect structure 80 of Figure 6 would be eliminated.

Figure 7 shows a cross section of another embodiment 110 corresponding to the electrical interconnection means 49 of Figure 1. Structure 110 has electrical conductors 112 which are clustered into groups 114. Between each group there are grooves 116. The elastomer material 118 is preferably a silicone elastomer and there are ball shaped contacts 120 on side 122 and flat contact 124 on side 126 having a raised surface 128. The top and bottom wire shapes can be varied for optimization. The alignment grooves 116 of structure 110 can be formed using a laser, electron beam or other sensing techniques as described in US Patent 4,998,885, to Beaman, the teaching of which is incorporated herein by reference.

Alignment features 116 can be molded into the elastomer material to allow accurate alignment of the conductors 112 in the structure 110 with contact locations 104 and 106 on surfaces 102 and 105, respectively, as shown in Figure 6. An alignment mechanism is preferred to enhance accurate positioning of the interposer wires with the contacts on the adjacent substrates. The molded alignment features can also be used to control the shrinkage and distortion of the contact grid in the elastomer material. Mechanically or thermally induced stress in the elastomer material can cause the interposer to distort causing alignment problems with the mating contacts.

The electrical interconnection means shown in Figures 5, 7 and 8 and electrical interconnection

means 49 of Figure 1 will also be referred to herein as an ELASTICON interposer.

The ELASTICON interposer is designed to provide signal and power connections from the bottom surface of a substrate to another substrate. The ELASTICON interposer can be fabricated to have a full array of conductors or a clustered array of conductors. The interposer connector that uses a full array of conductors (or wires) would typically not require alignment of the connector to the contact locations on the substrates between which is disposed. By using clusters of wires, overall fewer wires are used to fabricate the interposer. This is useful for reducing the cost of the connector and the pressure required to ensure full engagement of the contacts. Interposer contacts that use a clustered array of wires preferably have a means for aligning the wire clusters with the remaining said contacts. An interposer having a cluster set of wires minimizes the number of wires required during the interposer fabrication and enhances the compliance of the connector assembly. The molded or scribed grooves or other features in the elastomer material can be used to allow the interposer connector to self align with similar features on the substrates between which it is disposed as shown in Figure 8. Figure 8 shows interposer 119 disposed on substrate 121. Interposer 119 has grooves 123 which mate with projections 125 on substrate 121 which aligns substrate pads 127 to interposer contact locations 129. These alignment features can be designed using a variety of simple geometric shapes such as circular post, rectangular ridges, or a raised grid pattern. Figure 10 shows a perspective view of an ELASTICON interposer useful as the electrical interconnection means 49 of Figure 1. The ELASTICON interposer 134 of Figure 10 has a plurality of alignment grooves 136 and regions 138 containing clustered contacts wherein each region is surrounded by grooves 140.

Figure 9 shows an alignment frame 142 which is adapted for engagement with the grooves on the interposer 134 of Figure 10 to align substrate contact locations to interposer contact locations. For example, bar 144 in alignment frame 142 engages groove 146 of structure 134 of Figure 10 and bar 148 of frame 142 engages groove 150 of structure 134 of Figure 10. The frame is disposed on a substrate having contact locations to which interposer contact locations are to be aligned.

An overall alignment scheme is preferred to fabricate the structure of Figure 1. Each of the disconnectable elements of the module preferably have a means of alignment to the other elements in the module. A separate alignment frame could be attached to each substrate similar to the one used for the interposer.

Figures 11-19 show a fabrication method for the ELASTICON interposers described herein.

The fabrication process starts with a sacrificial substrate 160, which is preferably copper, copper/Invar/copper or copper/molybdenum copper. Materials other than copper can be used such as aluminum, hard plastic or steel. The substrate 160 can be fabricated to have protuberances 162 which provide the grooves 116 in the ELASTICON interposers of Figure 7. The protuberances 162 can be formed using various fabrication techniques including machining of the surface 164 or stamping of the surface 164. After the substrate has been formed with the protuberances, the top surface 164 is sputtered or plated with soft gold or Ni/Au to provide a suitable surface for thermosonic ball bonding. Other bonding techniques can be used such as thermal compression bonding, ultrasonic bonding, laser bonding and the like. A commonly used automatic wire bonder is modified to ball bond gold, gold alloy, copper, copper alloy, aluminum, nickel or palladium wires 166 to the substrate surface 164 as shown in Figure 11. The wire preferably has a diameter of 25 - 130  $\mu\text{m}$  (0.001 to 0.005 inches). If a metal other than Au is used, a thin passivation metal such as Au, Cr, Co, Ni or Pd can be coated over the wire by means of electroplating, or electroless plating, sputtering, e-beam evaporation or any other coating techniques known in the industry. Structure 168 of Figure 11 is the ball bonding head which has a wire 170 being fed from a reservoir of wire as in a conventional wire bonding apparatus. Figure 11 shows the ball bond head 168 in contact at location 169 with surface 164 of substrate 160.

Figure 12 shows the ball bonding head 168 withdrawn in the direction indicated by arrow 171 from the surface 164 and the wire 170 drawn out to leave disposed on the surface 164 wire 166. In the preferred embodiment, the bond head 168 is stationary and the substrate 160 is advanced as indicated by arrow 161. The bond wire is positioned at an angle preferably between 5 to 60° from vertical and then mechanically severed by knife edge 172 as shown in Figure 13. The knife edge 172 is actuated, the wire 170 is clamped and the bond head 168 is raised. When the wire 170 is severed there is left on the surface 164 of substrate 160 a flying lead 166 which is bonded to surface 164 at one end and the other end projects outwardly away from the surface. A ball can be formed on the end of the wire 166 which is not bonded to surface 164 using a laser or electrical discharge to melt the end of the wire. Techniques for this are commonly known in the art. A split beam laser delivery systems, described hereinbelow, is used to localize the laser energy to a single wire for forming the ball. This minimizes the

laser energy absorbed by adjacent wires that could cause the wires to deform. A ball is not required on the end of the wire. This modified wire bonding process is repeated to form a dense array of angled wires on the substrate.

Figure 14 shows the wire 170 severed to leave wire 166 disposed on surface 164 of substrate 160. The wire bond head 168 is retracted upwardly as indicated by arrow 174. The wire bond head 168 has a mechanism to grip and release wire 170 so that wire 170 can be tensioned against the shear blade to sever the wire.

Figure 15 shows that after the wire is severed, the bond head is raised to a "home" position. An electronic flame off unit (part of Hughes Wire Bonder, Model III-2640) electrode is positioned below the bond head and an electrical discharge from the electrode is used to melt the wire in the capillary tip to form a ball.

After the wire bonding process is completed, the substrate 160 is placed in a casting mold 190 as shown in Figure 16. A controlled volume of liquid elastomer 192 is disposed into the casting mold and allowed to settle out (flow between the wires until the surface is level) before curing as shown in Figure 17. Once the elastomer has cured, the substrate is extracted from the mold as shown in Figure 18 and indicated by arrow 194. The cured elastomer is represented by reference rule 196. Opening 161 in mold 190 is a tooling feature for extracting the substrate from the mold. The structure 198 is removed from the mold 190 and is placed in a sulfuric and nitric acid bath 200, as shown in Figure 19 to dissolve the copper substrate 160. Ultrasonic agitation of the sulfuric and nitric acid helps to facilitate the etching of the copper substrate and causes the gold plating on the surface of the copper substrate to flake off from the surface 202 of the elastomer material 196 leaving the surface of the ball bonds 204 exposed.

Alternatively, the substrate can be made of peel-apart-copper, where a thin layer of copper is attached to a solid substrate with a marginal adhesion strength. After the fabrication is completed, the connector can be peeled off from the sacrificial substrate before the remaining thin copper is flash etched away.

A high compliance, high thermal stability siloxane elastomer material is preferable for this application. The high temperature siloxane material is cast or injected and cured similar to other elastomeric materials. To minimize the shrinkage, the elastomer is preferably cured at lower temperature ( $T \leq 60^\circ$ ) followed by complete cure at higher temperatures ( $T \geq 80^\circ$ ). To further control the shrinkage, the connector is cast into a plastic frame, which was predrilled with holes around its periphery. When the elastomer is poured into this

frame a physical locking of the elastomer to the frame takes place which both holds the elastomer/connector to the frame and minimizes the shrinkage. To improve the compliance and reduce the dielectric constant of the elastomer material, a foam agent can be blended into the commercial elastomeric material at a ratio ranging from 10 to 60%. Also, foam can be employed as a distinct layer.

Among the many commercially available elastomers, such as ECCOSIL and SYLGARD, the use of polydimethylsiloxane based rubbers best satisfy both the material and processing requirements. However, the thermal stability of such elastomers is limited at temperatures below  $200^\circ\text{C}$  and significant outgassing is observed above  $100^\circ\text{C}$ . We have found that the thermal stability can be significantly enhanced by the incorporation of 25 wt % or more diphenylsiloxane (Figure 1). Further, enhancement in the thermal stability has been demonstrated by increasing the molecular weight of the resins (oligomers) or minimizing the crosslink junction. The outgassing of the elastomers can be minimized at temperatures below  $300^\circ\text{C}$  by first using a thermally transient catalyst in the resin synthesis and secondly subjecting the resin to a thin film distillation to remove low molecular weight side-products. For our experiments, we have found that 25 wt % diphenylsiloxane is optimal, balancing the desired thermal stability with the increased viscosity associated with diphenylsiloxane incorporation. The optimum number average molecular weight of the resin for maximum thermal stability was found to be between 18,000 and 35,000 g/mol. Higher molecular weights were difficult to cure and too viscous, once filled, to process. Network formation was achieved by a standard hydrosilylation polymerization using a hindered platinum catalyst in a reactive silicon oil carrier.

In Figure 11 when bond head 168 bonds the wire 170 to the surface 164 of substrate 160 there is formed a flattened spherical end shown as 204 in Figure 19. The protuberances 162 on substrate 160 as shown in Figure 11 result in grooves in the elastomer such as grooves 116 shown in Figure 7. These grooves form alignment features. The design and tolerances used to form the copper substrate 160 are preferably carefully matched with the design and tolerances used to fabricate the alignment features on the substrates 94 and 96 shown in Figure 6. Alternatively, on a substantially flat substrate, an alignment frame, such as shown in Figure 9, can be disposed on the surface of a substrate, such as 94 and 96, of Figure 6 and the elasticon interposer with grooves can be disposed onto this alignment frame so that the alignment grooves of the interposer engage the frame pattern



as describe herein above with respect to Figures 9 and 10.

Referring to Figure 20, multiple substrates 210 each having a group of wires 212 disposed thereon can be placed into a common mold 214 into which the liquid elastomer 216 as described herein above is disposed and cured. The cured elastomer links the substrates together into a single interposer 218 as shown in Figure 21. Grooves 211 are for compliance or alignment requirements. Alternatively, several smaller connectors can be fabricated on the same substrate as a single unit and then separated after the elastomer is cured and the substrate is etched away.

Also, the surface of the copper sacrificial substrate can be textured or embossed prior to gold plating and wire bonding to provide a textured or raised contact surface on the bottom of the ball bonds. The completed interposer 218 of Figure 21 can be further modified by using a laser to scribe channels in the elastomeric material between the bond wires at an angle matching the angled of the bond wires, as shown in Figure 7. The criss-crossing channels create independent elastomeric columns (shown in Figure 10 as 138) surrounding the gold wires. This would allow individual wires or groups of wires to compress independently and allow the interposer to compensate for slight variations in the remaining surfaces while reducing the total pressure required to compress the entire interposer. Patterned connectors can easily be fabricated by programming the wire bonder to a specific pattern and molding the elastomer to provide holes or open areas in the connector that correspond with other electronic or mechanical components surrounding the connector.

To improve compliance and reduce wire deformation, grooves are preferably molded into the elastomer on both sides of the connector surfaces in both the X and Y directions or in a circular geometry. The width and depth of the groove are preferably wider than 0.13 mm (5 mils) and deeper than 0.254 mm (10 mils), respectively, in an interposer 2.54 mm (100 mils) thick. The grooves are preferably molded in a direction parallel to the angled wire.

Grooves have been fabricated with laser, electron beam, metal mask and slicing with a blade. Other techniques such as stamping, injection molding and other known techniques to create the desired geometry would also work well.

The contact balls at the end of the wires are formed using a split beam laser configuration. The end of each wire will melt and form the ball only at the point where the two beams intersect. The design is illustrated in Figure 22 which shows light source 300, preferably an argon-ion laser which is the source of light beam 302 which is reflected as

light beam 304 by mirror 306. Light beam 304 is directed through light beam expander 308 to form expanded light beam 310. Expanded light beam 310 is directed to beam splitter 312 which splits beam 310 into beams 314 and 316. Beam 316 is reflected off mirror 322 as light beam 324. Beam 314 is reflected off mirror 318 as light beam 320. Beam 320 is passed through focusing lens 328 to form focused beams 330 which focused onto spot 332 on the workpiece which is the end of a wire. Beam 324 is passed through focussing lens 334 to form focused beam 336 which is focussed onto spot 332 on the workpiece. The workpiece is disposed on x-y table 338. The beam is expanded before focussing to get the desired size of spot 332.

Figure 23 shows an enlarged view of the region of Figure 7 enclosed in the dashed circle 230. Element 124 is a flattened ball shape member at the end of conductor 112. The flattened ball shaped member 124 was formed when conductor 112 was wire bonded to the sacrificial copper layer as described with reference to Figure 11. The sacrificial copper layer can be fabricated with an array of pits in the surface in the regions where the wires 112 are bonded. These pits can have, for example, a hemispherical shape, rectangular shape, pyramidal shape or any other shape. If such an array of pits are used and the wire is bonded in the region of the pit, a protuberance such as 128 of Figure 22 is formed at the surface 232 of flattened ball. This protuberance provides a projecting region to the contact formed by flattened ball 124 which can wipe on the surface of the contact location to which the flattened ball is to be electrically connected.

While the present invention has been described with respect to preferred embodiments, numerous modifications, changes and improvements will occur to those skilled in the art without the departing from the spirit and scope of the invention.

## Claims

1. A three dimensional electronic package structure (2) comprising:
  - a plurality of assemblies (4, 6);
  - each of said plurality of assemblies comprises a substrate (8) having a first and second opposing surface and a plurality of electronic devices (36, 38) disposed on at least one of said first and said second surfaces;
  - each of said plurality of assemblies is disposed adjacent another of said plurality of assemblies so that one of said first and said second opposing surfaces of one of said adjacent assemblies is adjacent one of said first

and said second opposing surfaces of the other of said adjacent assemblies;

an electrical interconnection means (49) is disposed between said adjacent assemblies (4, 6);

said electrical interconnection means (49) comprises a dielectric material having first and second opposing surfaces (48, 52) and a plurality of electrical conductors extending from said first to said second opposing surface of said electrical interconnection means;

said electrical interconnection means provides electrical interconnection between said adjacent assemblies.

2. The structure of claim 1, wherein said dielectric layer of said electrical interconnection means (49) is formed from an elastomeric material.
3. The structure of claims 1 or 2, further including a means for pressing said plurality of assemblies together so that said electrical interconnection means is compressed between said adjacent assemblies.
4. The structure of at least one of the preceding claims, further including a heat sink (51) in thermal communication with said substrates (8) of each of said plurality of assemblies.
5. The structure of at least one of the preceding claims, wherein said substrate (8) is selected from the group consisting of a ceramic substrate, a glass ceramic substrate, a diamond or diamond-like substrate material, a polymeric substrate, a glass substrate and a metal substrate and a silicon substrate, said substrate preferably being thermally conductive.
6. The structure of at least one of the preceding claims, wherein said electrical interconnection means (49) has a plurality of electrical contact locations (50, 54) on said first and said second opposing surfaces (48, 52) and wherein said conductors (e.g. in Fig. 2) are in electrical communication with said plurality of electrical contact locations.
7. The structure of claim 6, wherein said plurality of electrical contact locations are in electrical communication with a plurality of electrical contact locations on said adjacent assemblies.
8. The structure of at least one of the preceding claims, wherein said electrical interconnection means (49) comprise a layer of elastomeric material having a plurality of apertures extend-

ing from said first surface to said second surface of said layer (e.g. Fig. 3);

and wherein said electrical interconnection means is disposed on said first side of said first substrate so that said electronic devices on said first surface of said first substrate are disposed in said apertures in said electrical interconnection means,

so that said electrical contact locations on said second side of said layer of said electrical interconnection means are electrically interconnected with electrical contact locations on said first side of said substrate of said first assembly, and said electrical contact locations on said first side of said layer of said electrical interconnection means are electrically interconnected with electrical contact locations on said second side of said substrate of said second assembly.

9. The structure of at least one of the preceding claims, further including a means for pressing said first and said second assembly together to press said electrical interconnection means therebetween.
10. The structure of at least one of the preceding claims, further including a heat dissipation means in thermal contact with said structure or structure elements.
11. The structure of at least one of the preceding claims, wherein each of said plurality of electrical conductors has an enlarged end at said first and said second opposing surfaces of said electrical interconnection means (e.g. Fig. 5).
12. The structure of claim 11, wherein said enlarged end at one of said first and second opposing surfaces of said electrical interconnection means is sphere like.
13. The structure of claims 11 or 12, wherein said enlarged end at the other of said first and second opposing surfaces of said electrical interconnection means is hemisphere-like having a flattened face with a projection on said flattened face.
14. The structure of at least one of the preceding claims, wherein said elastomeric material has regions containing foam and solid materials, said regions preferably being a blend of foam and solid material.
15. A method for making an interconnection means for an electronic packaging structure comprising the steps of:

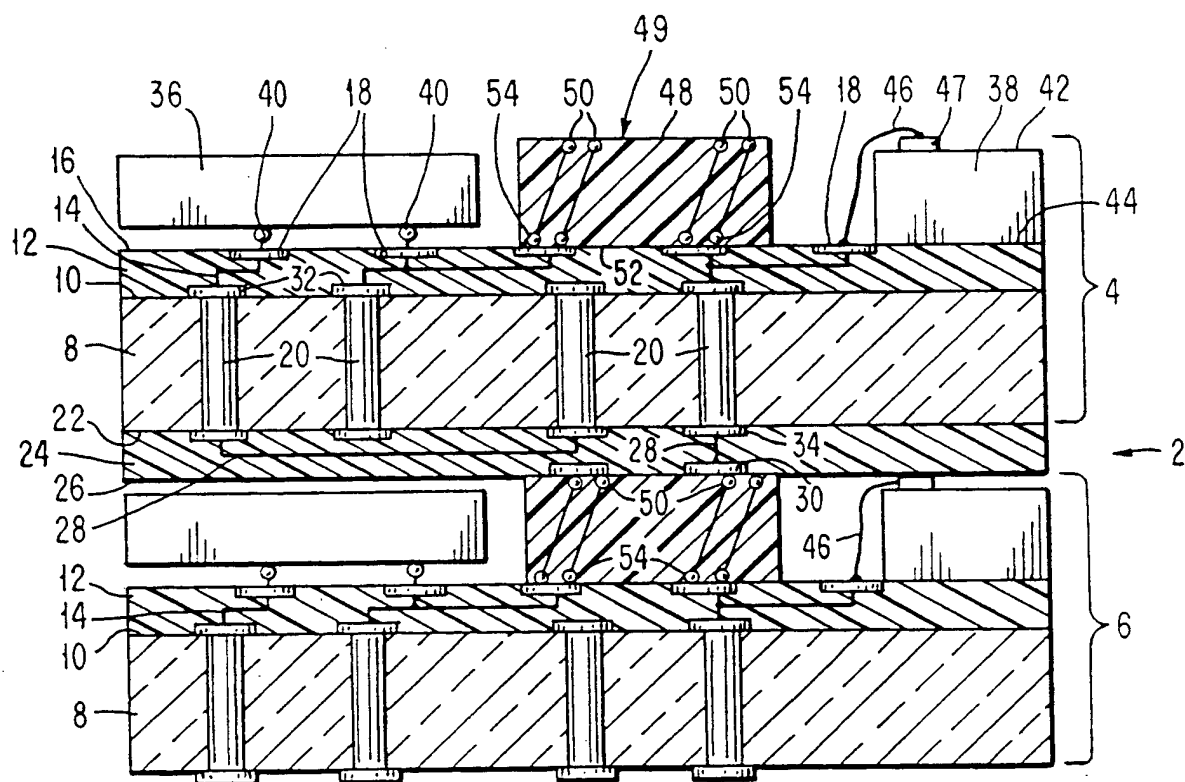
providing a substrate;  
 providing a plurality of elongated conductors  
 each having a first end and a second end;  
 bonding said first end of each of said plurality  
 of conductors to said substrate;  
 said second ends of said plurality of elongated  
 conductors projects away from said substrate;  
 placing said substrate in a mold;  
 adding to said mold a liquid material;  
 curing said liquid to a solid body having said  
 plurality of elongated conductors disposed  
 therein;  
 removing said solid body from said mold;  
 removing said substrate from said solid body  
 leaving said solid body with said elongated  
 conductors extending there through; and  
 said first and said second ends of said elon-  
 gated conductors being exposed at the surface  
 of said solid body (Figs. 11-21).

16. The method of claim 15, wherein said sub-  
 strate is a laminated substrate formed from a  
 material selected from the group consisting of  
 Cu and laminated with one or more of molyb-  
 denum, invar and a composite thereof with a  
 polymer layer. 25
17. The method of claims 15 or 16, wherein said  
 substrate has projections which result in cav-  
 ities in said solid body, said projections prefer-  
 ably being formed by stamping said substrate. 30
18. The method of claim 15, wherein said step of  
 removing said substrate is etching said sub-  
 strate. 35
19. The method of at least one of claims 15 to 18,  
 further including forming an enlargement at  
 said first and/or second end of said elongated  
 conductor. 40
20. The method of at least one of claims 15 to 19,  
 wherein said substrate is formed from peel-  
 apart-copper wherein a thin layer of copper is  
 attached to a sacrificial substrate with a mar-  
 ginal adhesion strength and wherein said layer  
 of copper is peeled off from said sacrificial  
 substrate. 45
21. The method of at least one of claims 15 to 20,  
 wherein said substrate has pits resulting in  
 projections on said solid body onto which said  
 first end of at least a part of said plurality of  
 conductors is bonded. 50
22. The method of at least one of claims 15 to 21,  
 wherein said elongated conductor is formed  
 from a material selected from the group con- 55

sisting of Au, Cu, Al, Ag, Ni and alloys thereof.

23. The method of at least one of claims 15 to 22,  
 wherein said elongated conductor has a thin  
 surface layer of a material selected from the  
 group consisting of Au, Cr, Co, Ni, Pd and Pt,  
 said surface layer being preferably deposited  
 by a method selected from the group consist-  
 ing of electroplating, electroless plating, sput-  
 tering and e-beam evaporation.
24. The method of at least claim 15, wherein said  
 step of curing comprises a first cure at a  
 temperature less than about 60°C and a sec-  
 ond curing at a temperature of greater than  
 about 80°C.
25. The method of at least claim 15, further includ-  
 ing a frame on said mold to minimize shrinking  
 during said step of curing.
26. The method of at least claim 15, wherein said  
 liquid includes a foaming agent.

FIG. 1



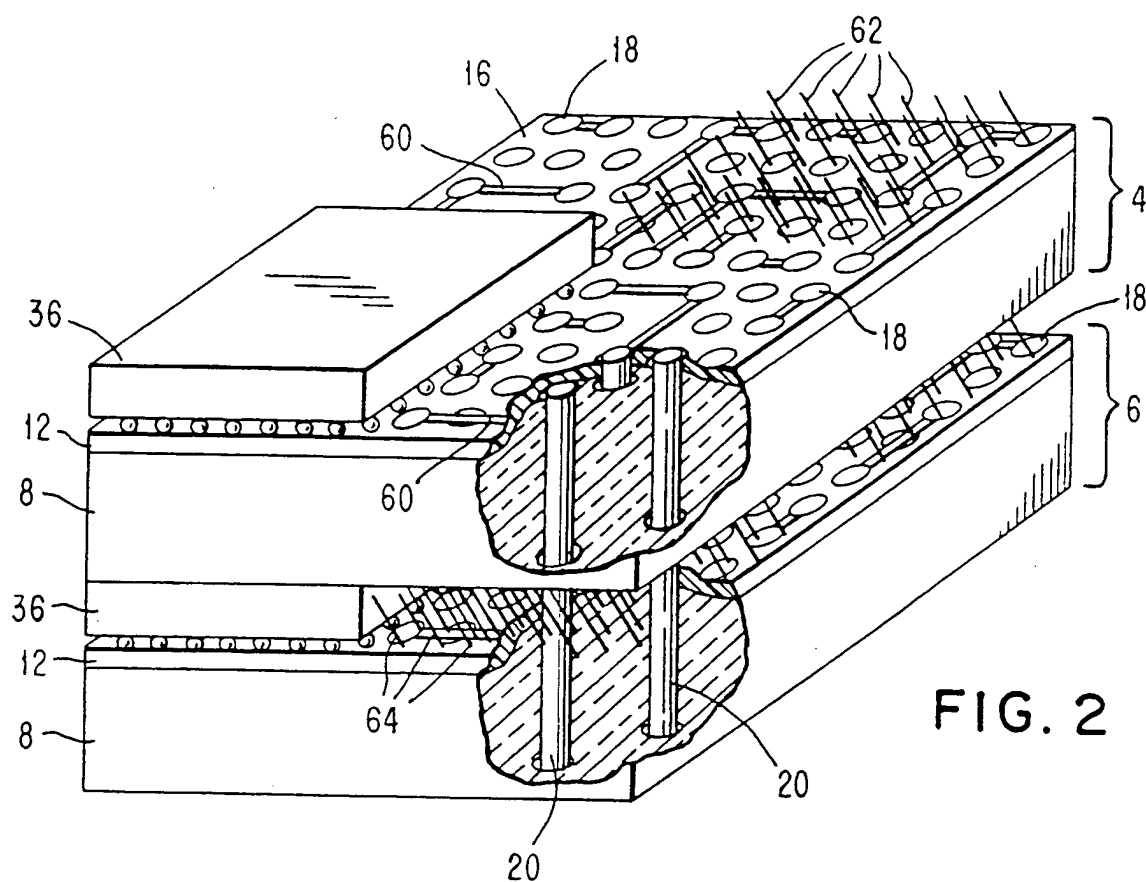
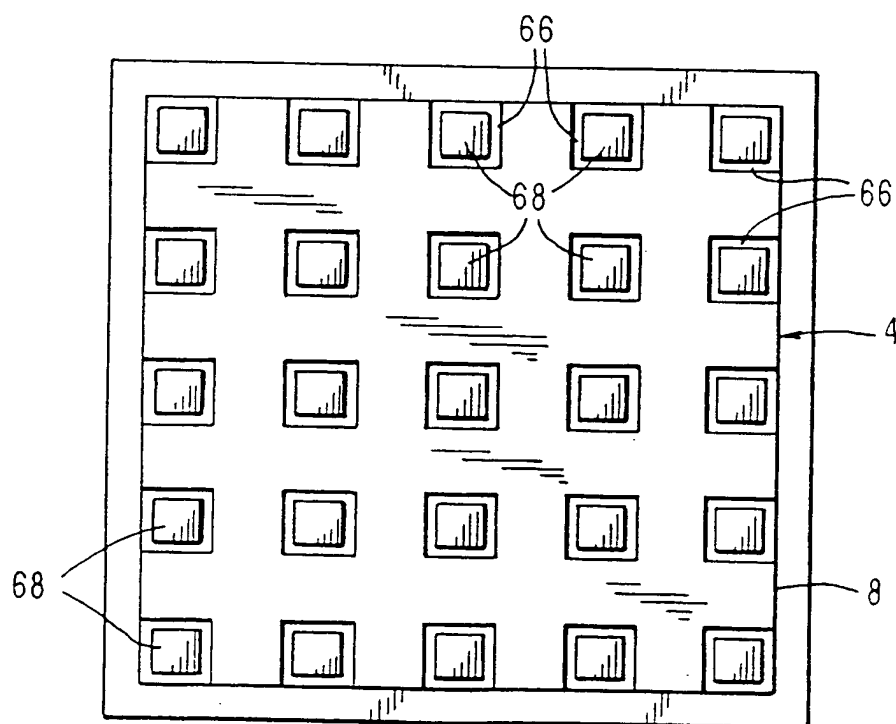


FIG. 3



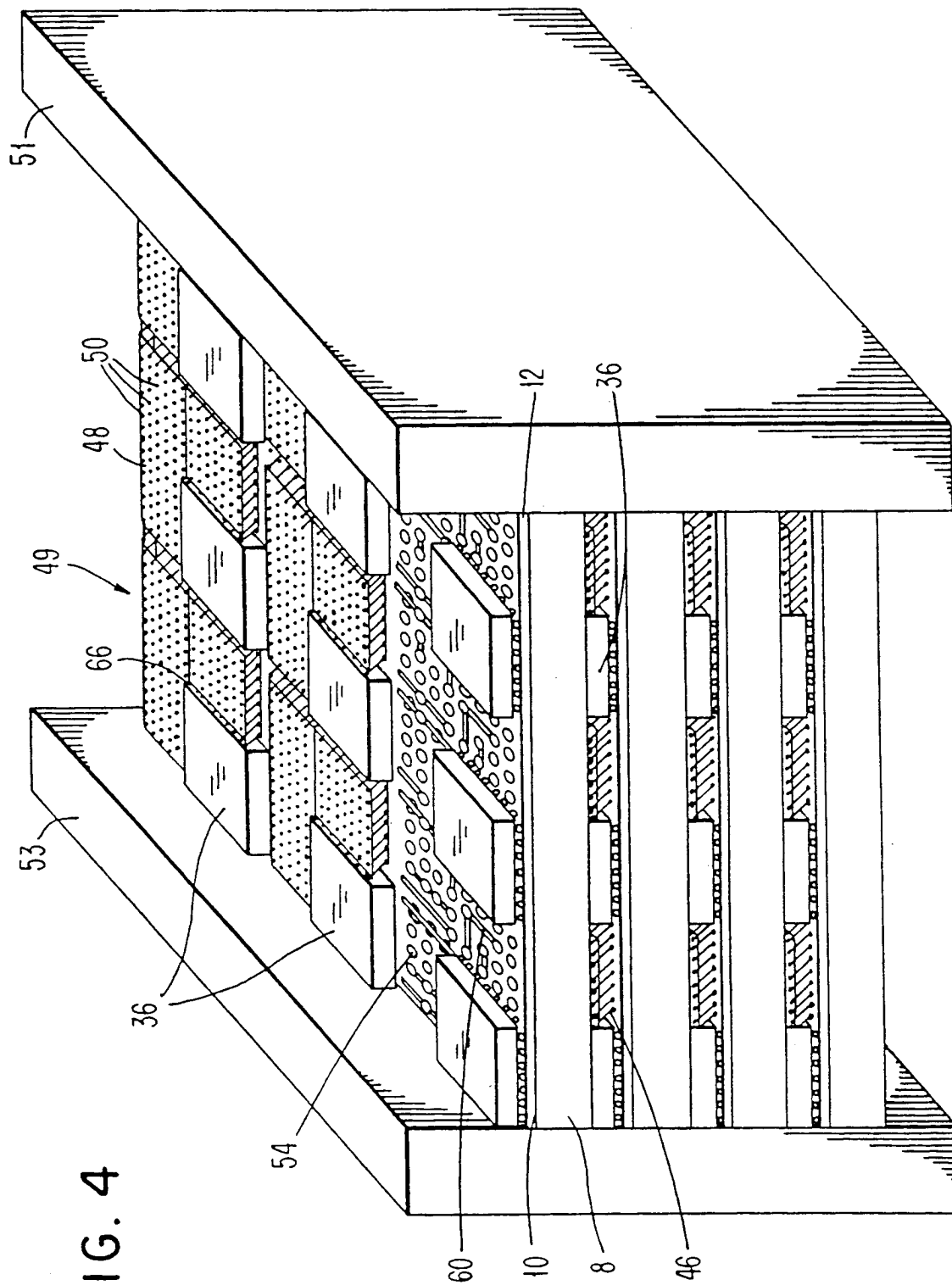


FIG. 4

FIG. 5

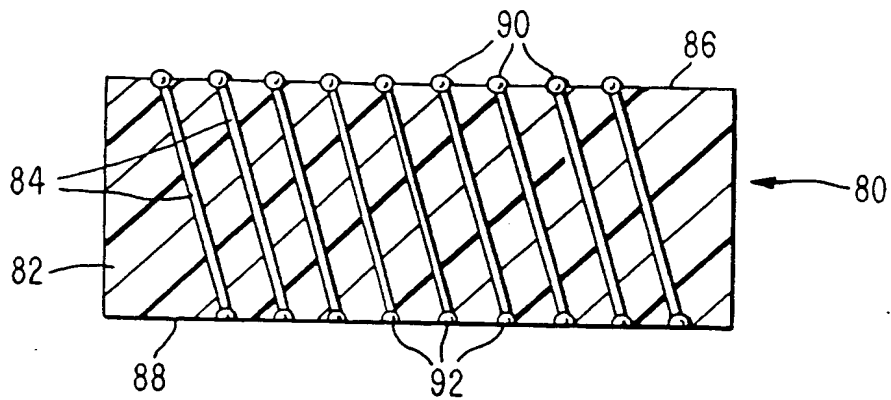


FIG. 6

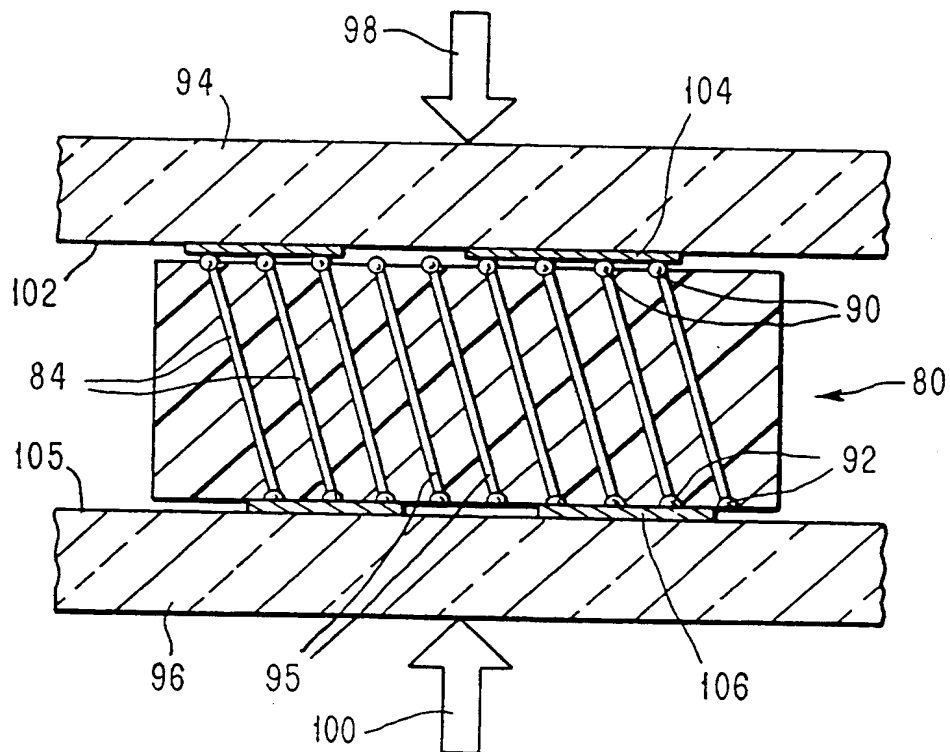


FIG. 7

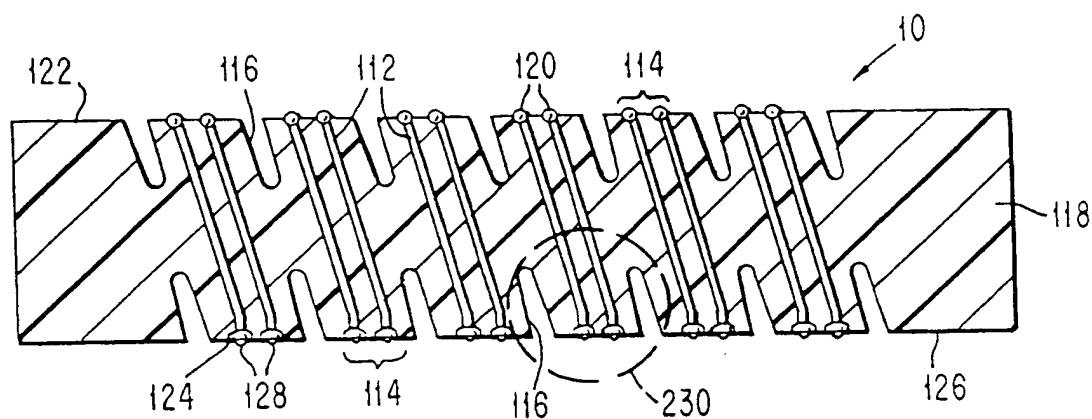


FIG. 8

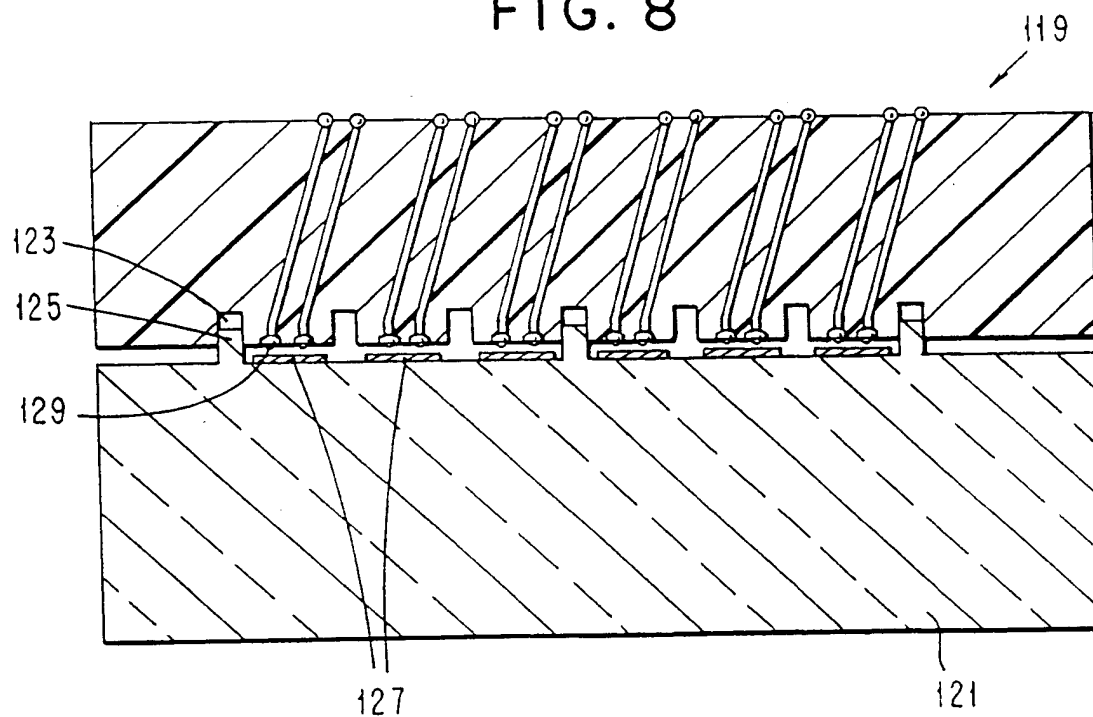




FIG. 9

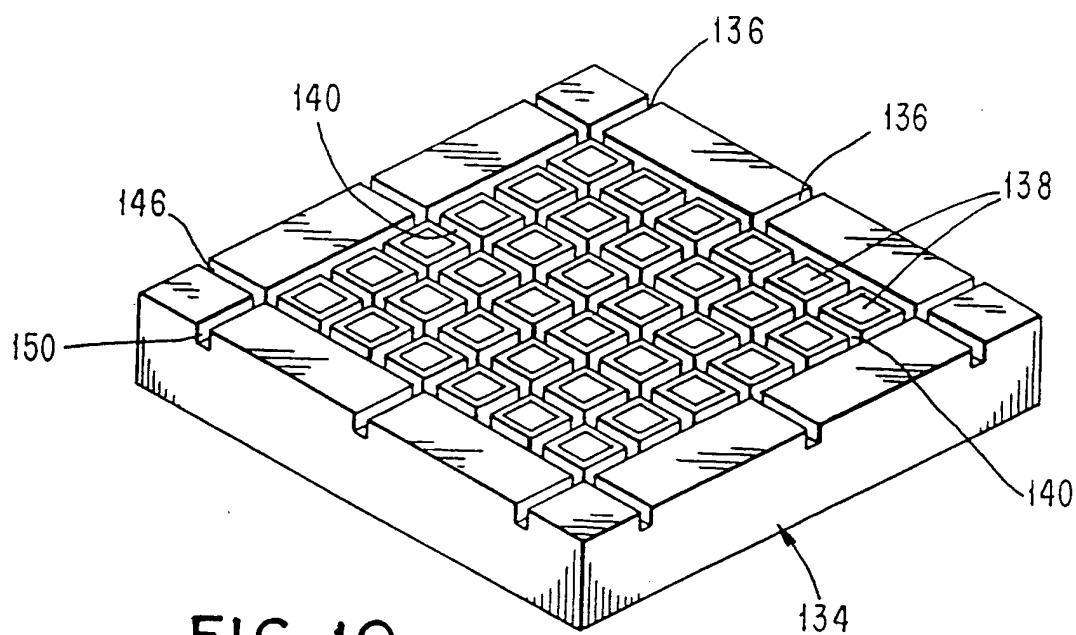
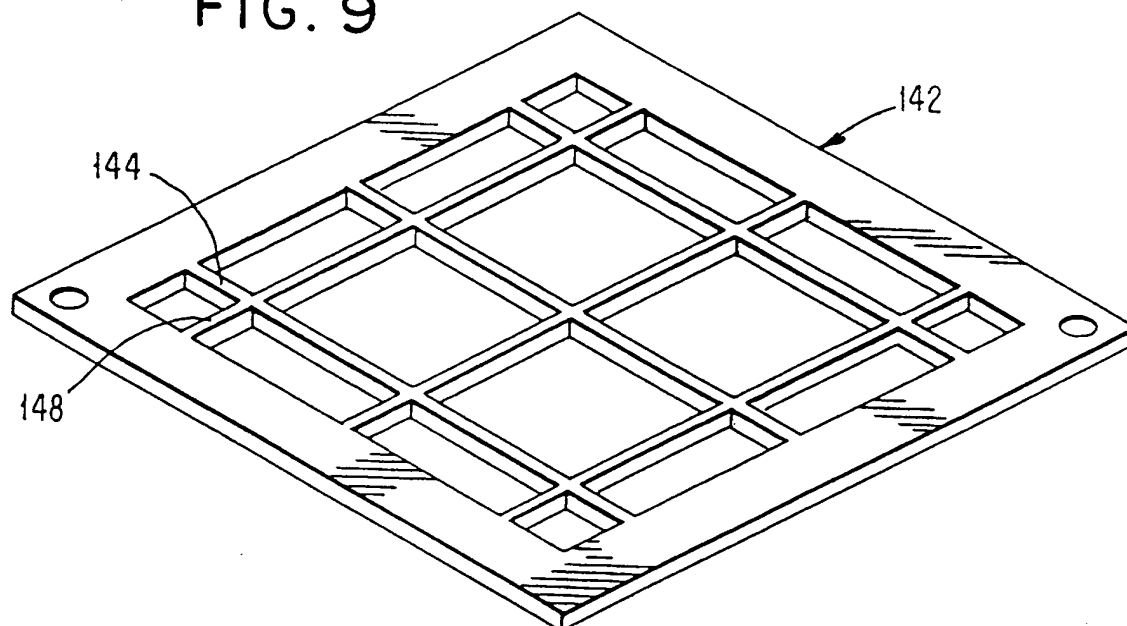


FIG. 10

FIG. 11

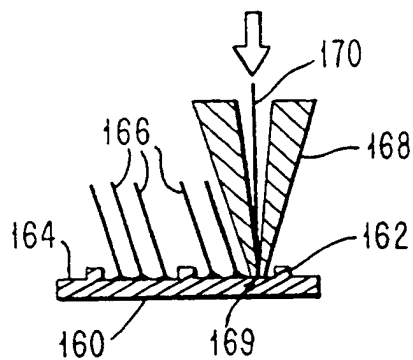


FIG. 12

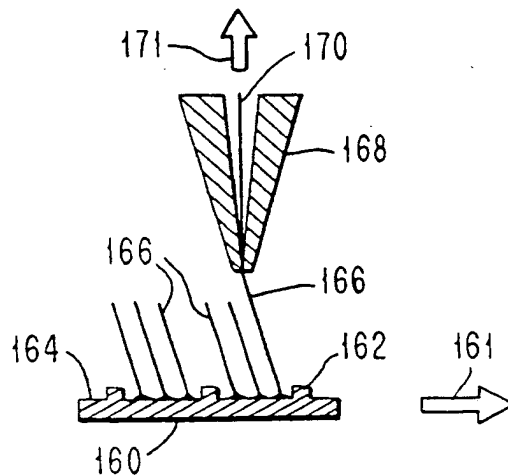


FIG. 13

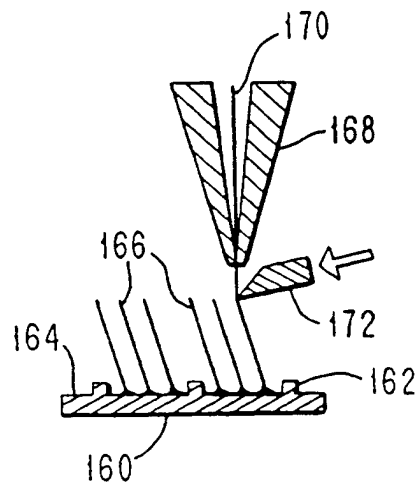


FIG. 14

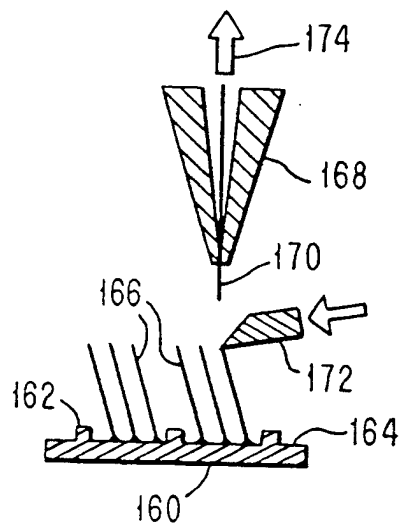


FIG. 15

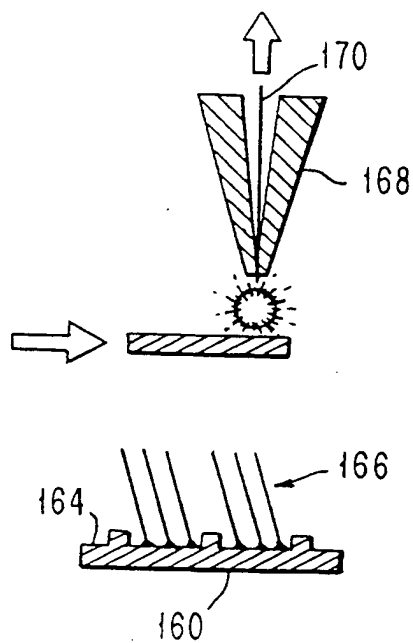


FIG. 16

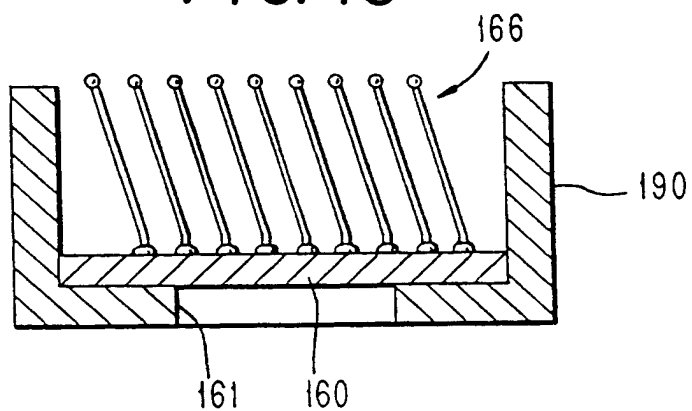


FIG. 17

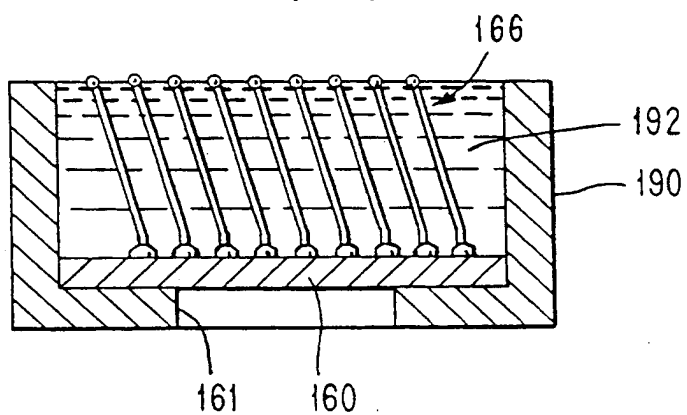


FIG. 18

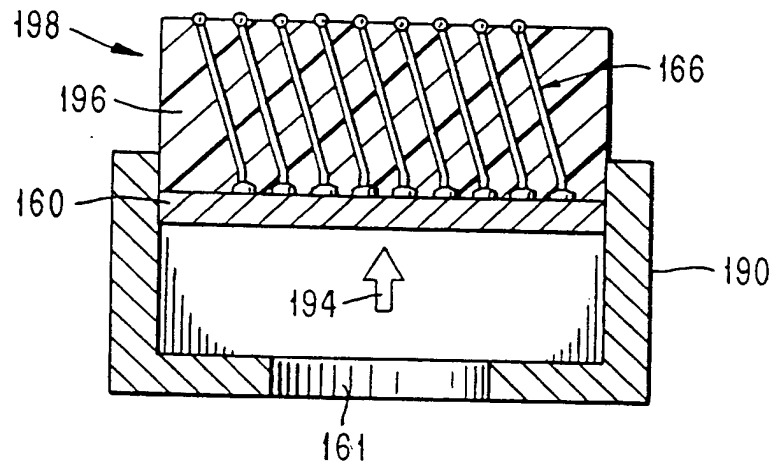
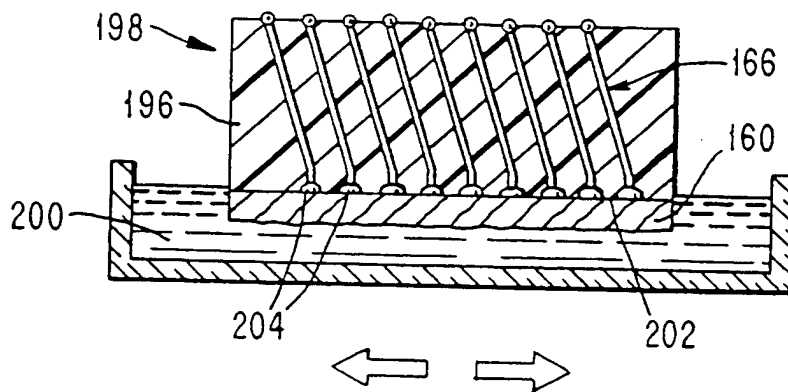


FIG. 19



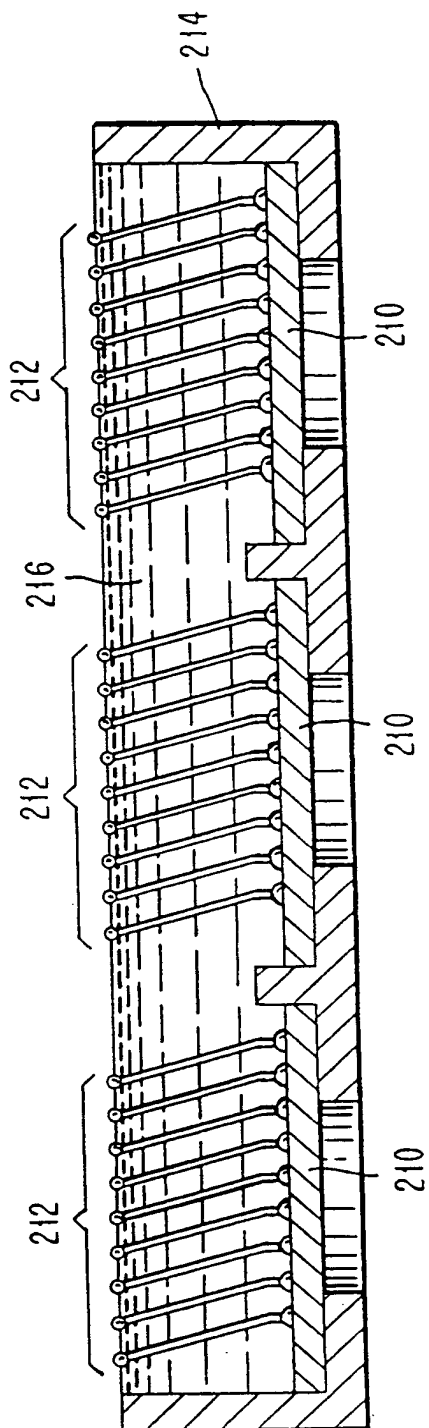


FIG. 20

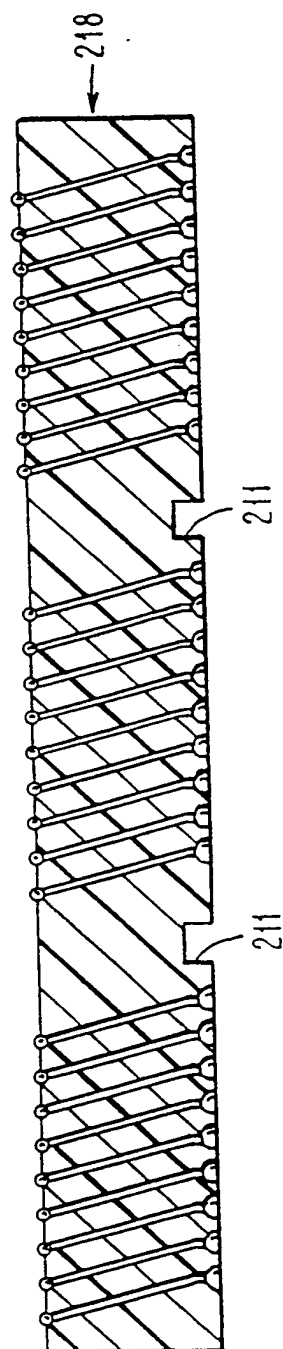


FIG. 21

FIG. 22

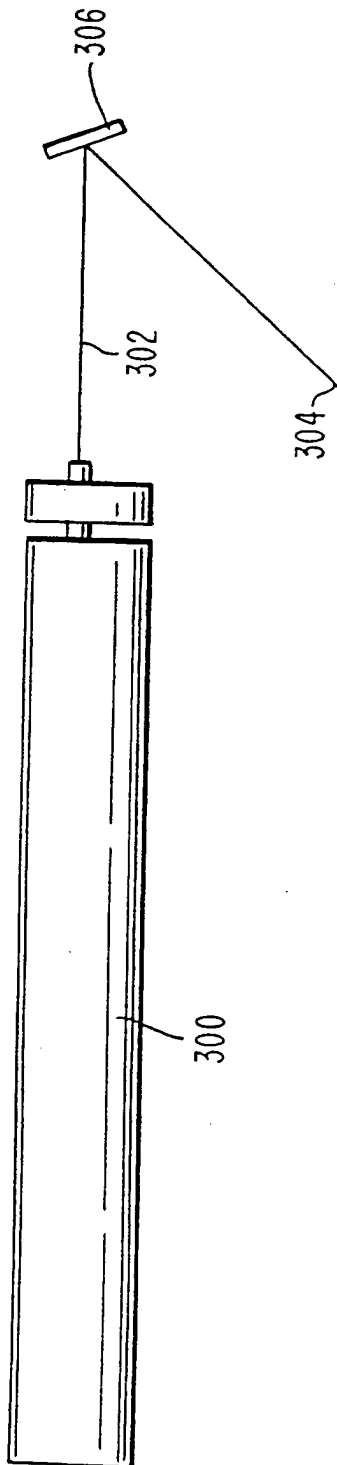
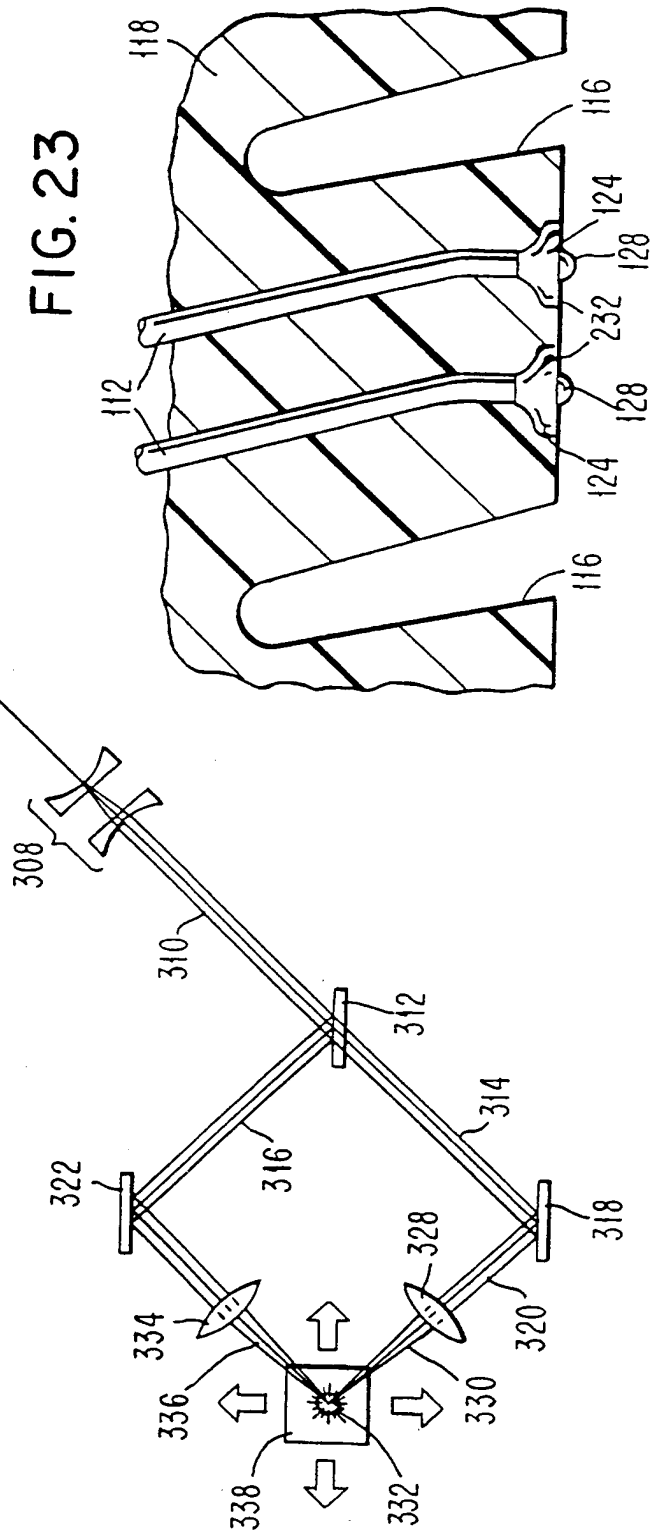


FIG. 23





European Patent  
Office

## EUROPEAN SEARCH REPORT

Application Number  
EP 93 11 5996

DOCUMENTS CONSIDERED TO BE RELEVANT			
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int.Cl.5)
Y A	EP-A-0 281 900 (IBM) * claims 1,3; figure 1 * ----	1 2,5-8,14	H01L23/538 H01L25/065
Y	EP-A-0 472 451 (THOMSON) * claims 1,6-8,10; figure 7 * ----	1	
D,A	US-A-5 099 309 (IBM) * claims 1,7; figure 4 * ----	1,3,4	
D,A	US-A-4 998 885 (IBM) * claim 1; figures 1,8 * ----	2,15	
A	EP-A-0 268 111 (IBM) -----		
			TECHNICAL FIELDS SEARCHED (Int.Cl.5)
			H01L
The present search report has been drawn up for all claims			
Place of search		Date of completion of the search	Examiner
THE HAGUE		6 December 1993	De Raeve, R
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T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons ..... & : member of the same patent family, corresponding document			